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	Application No.	Applicant(s)	
	10/763,688	CHAN ET AL.	
Notice of Allowability	Examiner	Art Unit	
	DuyVu n. Deo	1765	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.			
1. This communication is responsive to the paper filed 1/25/06.			
2. The allowed claim(s) is/are <u>1-16</u> .			
 3. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some* c) None of the: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this national stage application from the 			
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.			
4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.			
$5.\ \square$ CORRECTED DRAWINGS (as "replacement sheets") mus	it be submitted.		
(a) including changes required by the Notice of Draftspers	on's Patent Drawing Review (PTO-	948) attached	
1) hereto or 2) to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).			
6. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.			
Attachment(s) 1. ☑ Notice of References Cited (PTO-892)	5 ☐ Notice of Informal P	atent Application (PTO-152)	
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Summary	(PTO-413),	
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0-Paper No./Mail Date 1/23/04	Paper No./Mail Date 98), 7. ⊠ Examiner's Amendm	e nent/Comment	
4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. Examiner's Stateme	ent of Reasons for Allowance	
o Diological Material	9.		
		Primary Examiner Duy-Vu N. Deo	

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DETAILED ACTION

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows: the examiner cancels 17-22 since they are withdrawn without traverse in the paper filed 1/25/06.

Allowable Subject Matter

2. The following is an examiner's statement of reasons for allowance:

Prior art doesn't suggest or teach the limitations of independent claims 1 and 15.

Claim 1: A method for forming a semiconductor device comprising:

providing a structure of a semiconductive material with a hardmask thereover, said hardmask having at least one tapered portion with a corresponding portion of a further film disposed thereover;

etching an uncovered portion of said hardmask to expose an exposed portion of said semiconductive material while maintaining said at least one tapered portion and each said corresponding portion substantially intact, and

etching said exposed portion of said semiconductive material while maintaining said at least one tapered portion and each said corresponding portion substantially intact.

Claim 15: A method for forming a semiconductor device comprising:

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providing a layer of hardmask material over a semiconductor substrate,

forming a photoresist pattern over said layer of hardmask material,

etching to produce a discrete portion of said hardmask material, said discrete portion having at least one tapered section with a taper angle within the range of 450 to 850 with respect to a surface of said semiconductor substrate,

carrying out a photoresist strip process,

forming an oxide layer over said discrete portion;

removing portions of said oxide layer and planarizing to produce said discrete portion having a substantially planar uncovered portion and each tapered section having a corresponding portion of said oxide layer thereover.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to DuyVu n. Deo whose telephone number is 571-272-1462. The examiner can normally be reached on 6:00-2:30 Mon-Fri.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Primary Examiner Duy-Vu N. Deo 2/16/06

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